

In the Claims:

Claim 1 (amended). A method of producing an electrode configuration, which comprises the following steps:

forming a first conductive layer of a material which is substantially unetchable by chemical dry-etching;

forming a second conductive layer on the first conductive layer from a material which is etchable by chemical dry-etching;

structuring the second conductive layer to form a structured second layer; and

chemical-physical dry etching the first conductive layer while using the second structured layer as a mask.